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10/626,336

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EXAMINER

NADAV, ORI

ART UNIT

PAPER NUMBER

2811

DATE MAILED: 03/30/2005

Please find below and/or attached an Office communication concerning this application or proceeding.



### DETAILED ACTION

Applicant's request for reconsideration of the finality of the rejection of the last Office action is persuasive and, therefore, the finality of that action is withdrawn.

### ***Claim Rejections - 35 USC § 103***

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claims 7-8 and 10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Adan (5,198,379) in view of Mizutani et al. (Jp 2001123293A).

Adan teaches in figure 4 an oxide layer 2A formed directly on a semiconductor substrate, and an oxide layer 4A formed on a bottom gate 6A.

Adan does not teach forming the oxide layers by a method comprising forming a metallic precursor and then oxidizing said metallic precursor in a liquid oxidizer.

Mizutani et al. teach in figure 1 and related text a method of forming an oxide layer comprising: forming a metallic precursor 3, 4 directly on a substrate 1 and oxidizing said metallic precursor in a liquid oxidizer (abstract).

It would have been obvious to a person of ordinary skill in the art at the time the invention was made to form Adan's oxide layers by Mizutani et al.'s method which comprises forming a metallic precursor and then oxidizing said metallic precursor in a

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liquid oxidizer, in order to provide better insulation to the gate of the device. The combination is motivated by the teachings of Mizutani et al. who point out the advantages of using his oxide layer to protect the gate in a TFT device (paragraph 31). Note that forming Mizutani et al.'s oxide layer in Adan's device meets the claimed limitation of forming a metallic precursor directly on a semiconductor substrate.

Claims 9 and 11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Mizutani et al. and Adan, as applied to claims 7 and 10 above, and further in view of Yao (6,679,996).

Regarding claim 11, Mizutani et al. and Adan teach substantially the entire claimed structure, as applied to claim 7 above, except forming the metal oxide dielectric of hafnium, zirconium, or tantalum.

Yao teaches in figure 1A forming the metal oxide dielectric 3 of hafnium, zirconium, or tantalum (column 4, lines 18-30).

It would have been obvious to a person of ordinary skill in the art at the time the invention was made to form the metal oxide dielectric of hafnium, zirconium, or tantalum, in Mizutani et al. and Adan's device, in order to use the appropriate material for the application in hand. Note that substitution of materials is not patentable even when the substitution is new and useful. *Safetran Systems Corp. v. Federal Sign & Signal Corp.* (DC NIII, 1981) 215 USPQ 979.

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Regarding claim 9, Yao teaches using a liquid oxidizer includes using an oxidizer in an aqueous solution (column 3, line 24).

Claim 12 is rejected under 35 U.S.C. 103(a) as being unpatentable over Mizutani et al. and Adan, as applied to claims 7 and 10 above, and further in view of Garcia (5,836,150).

Mizutani et al. and Adan teach substantially the entire claimed structure, as applied to claim 7 above, except using physical vapor deposition to deposit metal atoms.

Garcia teaches using physical vapor deposition or chemical vapor deposition to deposit metal atoms (column 4, lines 29-33).

It would have been obvious to a person of ordinary skill in the art at the time the invention was made to use physical vapor deposition to deposit metal atoms, in Mizutani et al. and Adan's device, in order to use the most suitable conventional vapor deposition for the application in hand.

Claim 13 is rejected under 35 U.S.C. 103(a) as being unpatentable over Mizutani et al. and Adan, as applied to claims 7 and 10 above, and further in view of Tsuzumitani et al. (6,645,807).

Mizutani et al. and Adan teach substantially the entire claimed structure, as applied to claim 7 above, except using a liquid oxidizer selected from the group including solutions of O<sub>3</sub>, H<sub>2</sub>O<sub>2</sub> and organic peroxide.

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Tsuzumitani et al. teach in figure 1 and related text forming a metal oxide dielectric 7A using a liquid oxidizer selected from the group including solutions of O<sub>3</sub>, H<sub>2</sub>O<sub>2</sub> and organic peroxide (column 7, lines 42-45).

It would have been obvious to a person of ordinary skill in the art at the time the invention was made to use a liquid oxidizer selected from the group including solutions of O<sub>3</sub>, H<sub>2</sub>O<sub>2</sub> and organic peroxide, in Mizutani et al. and Adan's device, in order to use the appropriate material for the application in hand. Note that substitution of materials is not patentable even when the substitution is new and useful. *Safetran Systems Corp. v. Federal Sign & Signal Corp.* (DC NIII, 1981) 215 USPQ 979.

### ***Response to Arguments***

Applicant's arguments with respect to claims 7-13 have been considered but are moot in view of the new ground(s) of rejection.

### ***Conclusion***

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire **THREE MONTHS** from the mailing date of this action. In the event a first reply is filed within **TWO MONTHS** of the mailing date of this final action and the advisory action is not mailed until after the end of the **THREE-MONTH** shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than **SIX MONTHS** from the date of this final action.

**Papers related to this application may be submitted to Technology center (TC) 2800 by facsimile transmission. Papers should be faxed to TC 2800 via the TC 2800 Fax center located in Crystal Plaza 4, room 4-C23. The faxing of such papers must conform with the notice published in the Official Gazette, 1096 OG 30 (November 15, 1989). The Group 2811 Fax Center number is (703) 308-7722 and 308-7724. The Group 2811 Fax Center is to be used only for papers related to Group 2811 applications.**

Any inquiry concerning this communication or any earlier communication from the Examiner should be directed to *Examiner Nadav* whose telephone number is **(571) 272-1660**. The Examiner is in the Office generally between the hours of 7 AM to 4 PM (Eastern Standard Time) Monday through Friday.

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Any inquiry of a general nature or relating to the status of this application should be directed to the **Technology Center Receptionists** whose telephone number is **308-0956**

A handwritten signature in black ink, appearing to read 'Ori Nadav', with a stylized, sweeping flourish at the end.

O.N.  
3/23/05

ORI NADAV  
PRIMARY EXAMINER  
TECHNOLOGY CENTER 2800